



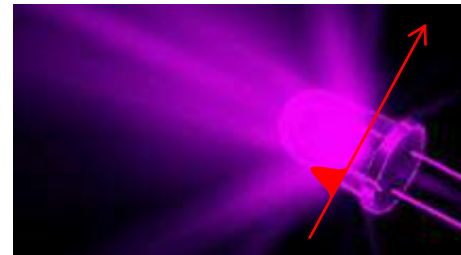
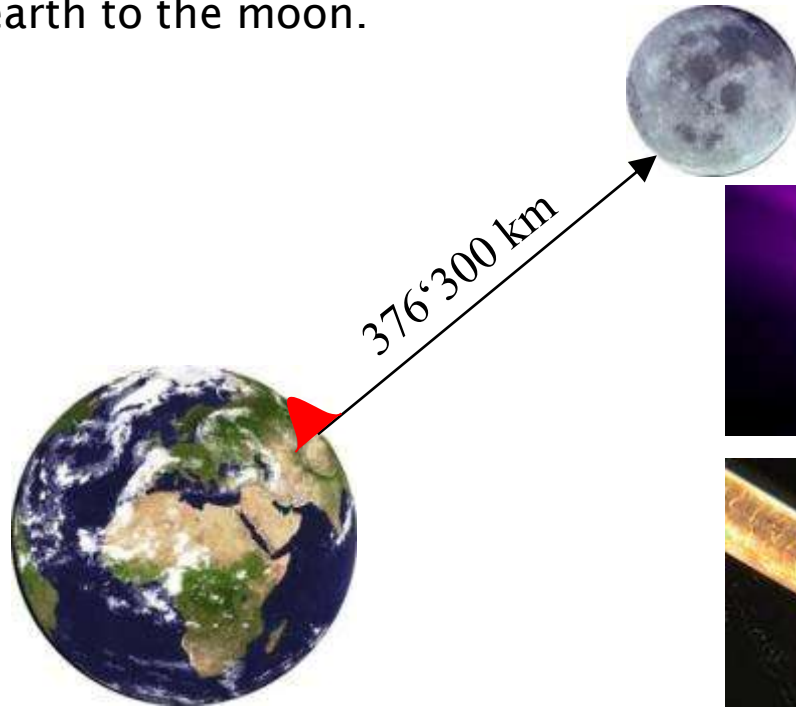
Berner Fachhochschule  
Haute école spécialisée bernoise  
Bern University of Applied Sciences

# Ultra-short laser pulses in micro-processing: Myth, a next generation technology or already reality?

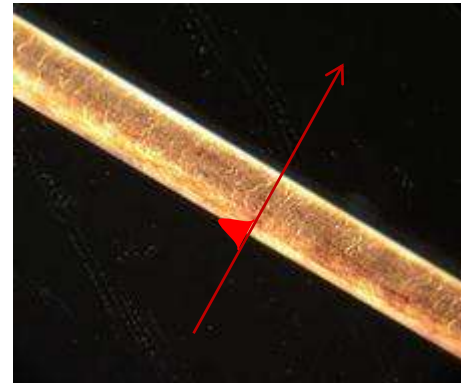
B. Neuenschwander

# What means ultra-short?

Light needs 1.25s for travelling the distance from the earth to the moon.



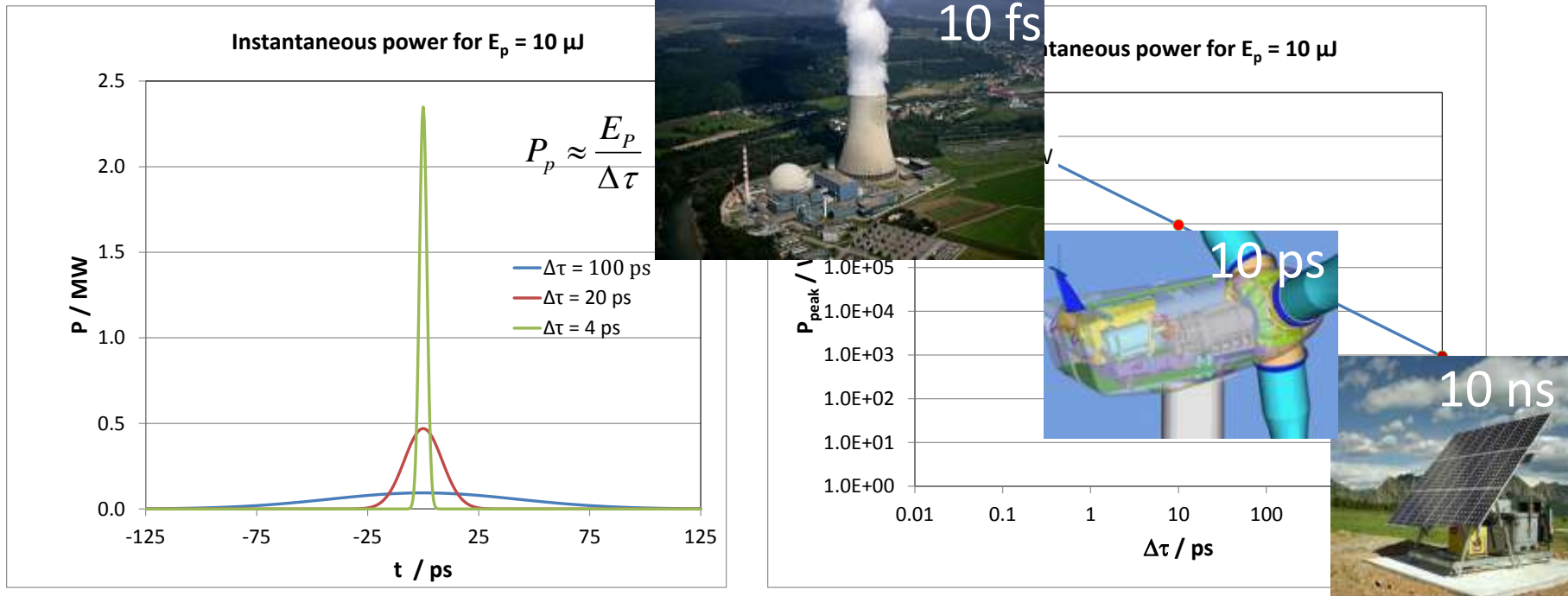
The diameter of a small LED amounts 3 mm:  
For travelling 3 mm light needs 10 ps ( $10 \cdot 10^{-12}$  s)



Human hair, thickness ca. 60  $\mu$ m:  
For travelling 60  $\mu$ m light needs 200 fs ( $200 \cdot 10^{-15}$  s)

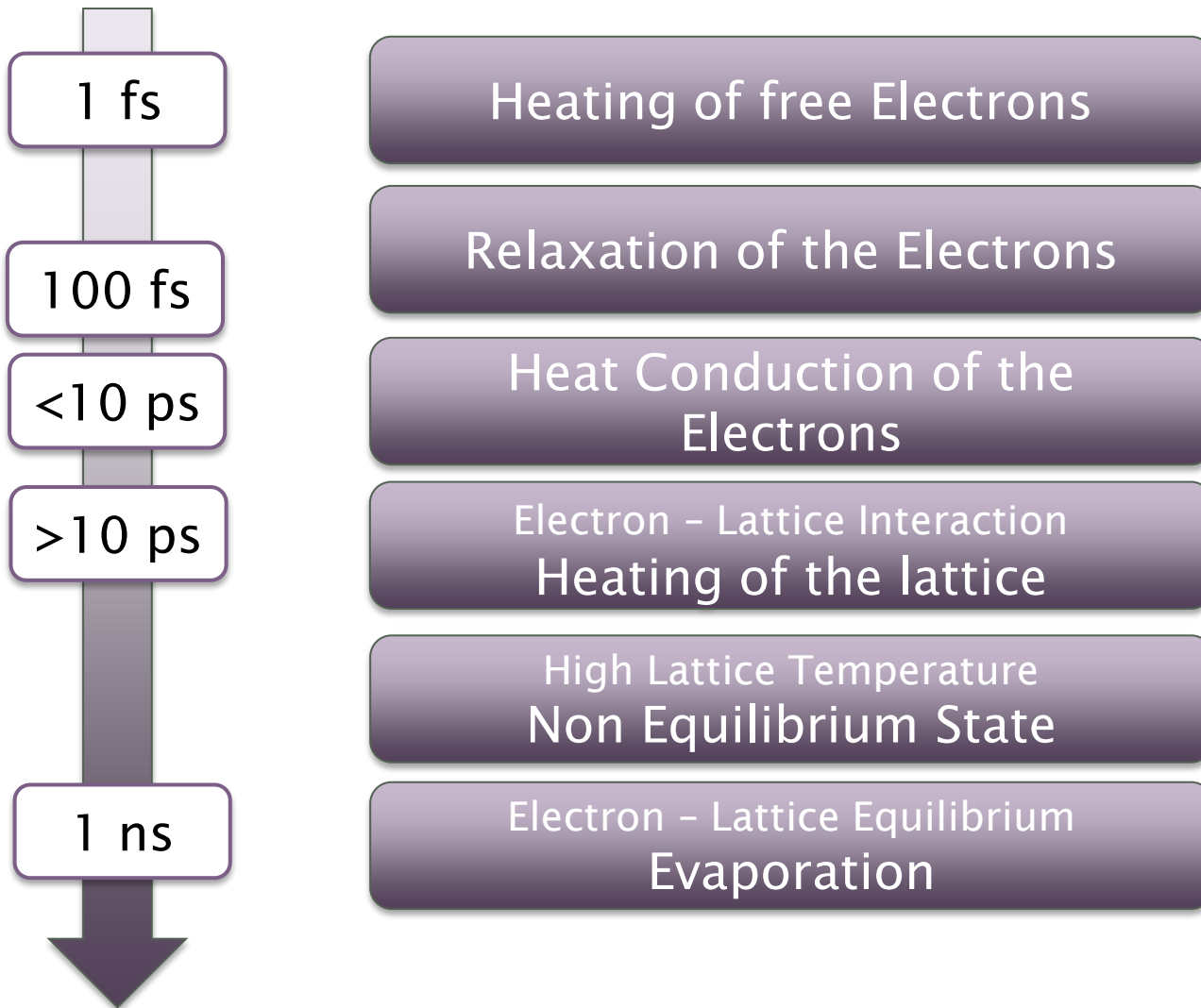
**Ultra-short laser pulses are really short!**

# What means ultra-short?

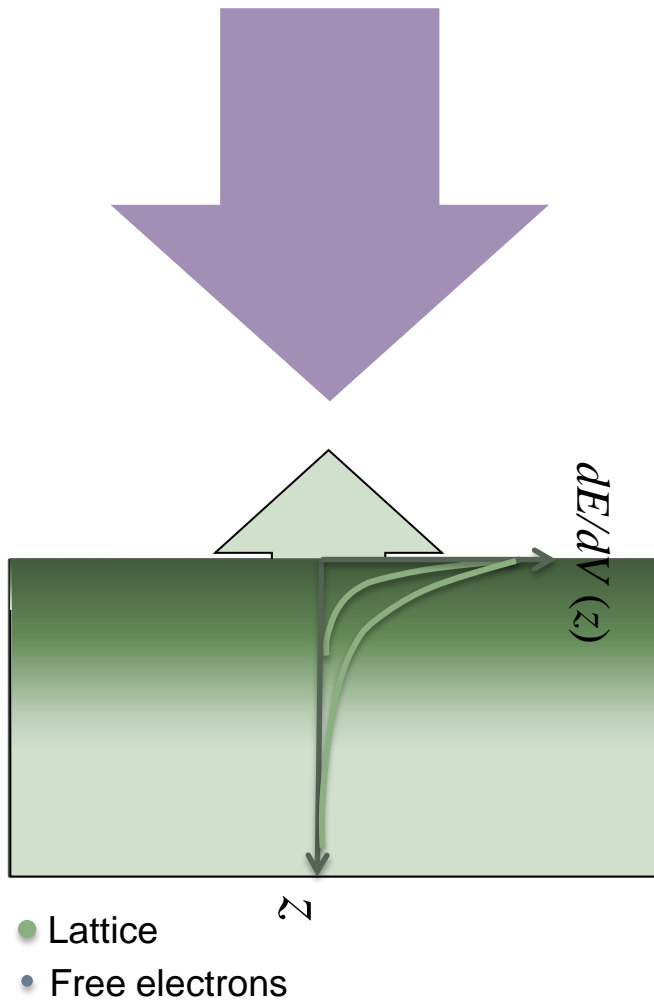


**Even with small pulse energies huge peak powers can be achieved with ultra-short pulses.**

# Laser – Matter interaction times (metals)



# Model of the ablation process: Energy transport



The incoming laser pulse

- is absorbed by the free electrons
- the energy is transferred to the lattice
- and the material is removed (ablated)

The energy transport into the material is described with the two temperature model.

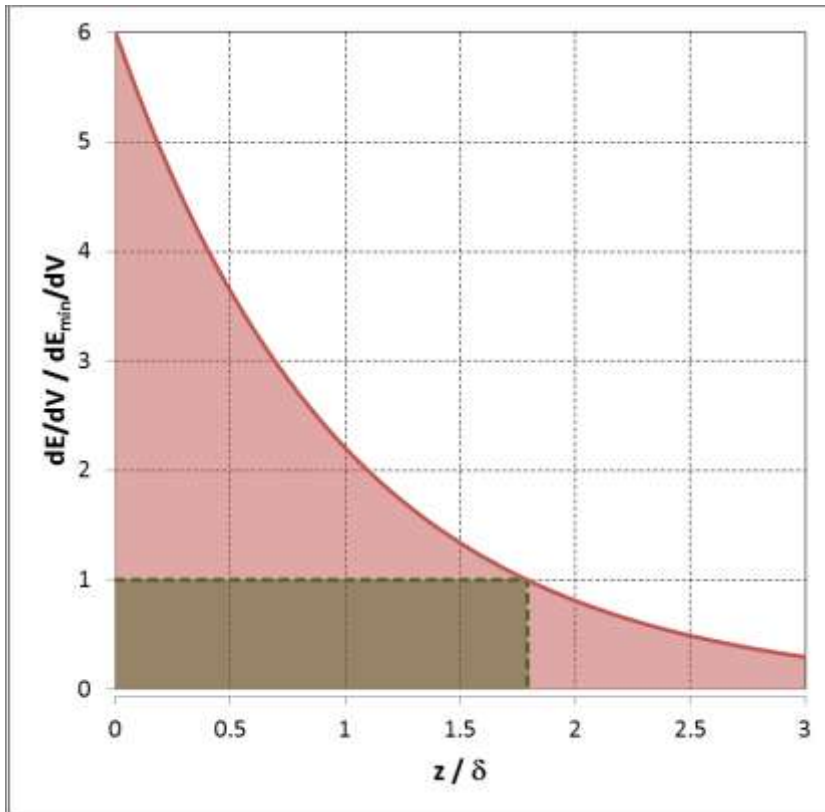
The deposited energy per volume exponentially drops with the distance to the surface. Depending on the pulse duration and the applied fluence the corresponding penetration depth is dominated by

- optical penetration depth

or by the

- the thermal diffusion length of the free electrons

# Top Hat: Ablation Efficiency



The deposited energy per unit volume exponentially drops with the distance  $z$  to the surface.

$$\frac{dE}{dV}(z) = \frac{dE_0}{dV} \cdot e^{-\frac{z}{\delta}}$$

To evaporate the material a minimum energy per unit Volume  $\rho \cdot \Omega_{vap}$ , is required, which defines the ablation depth

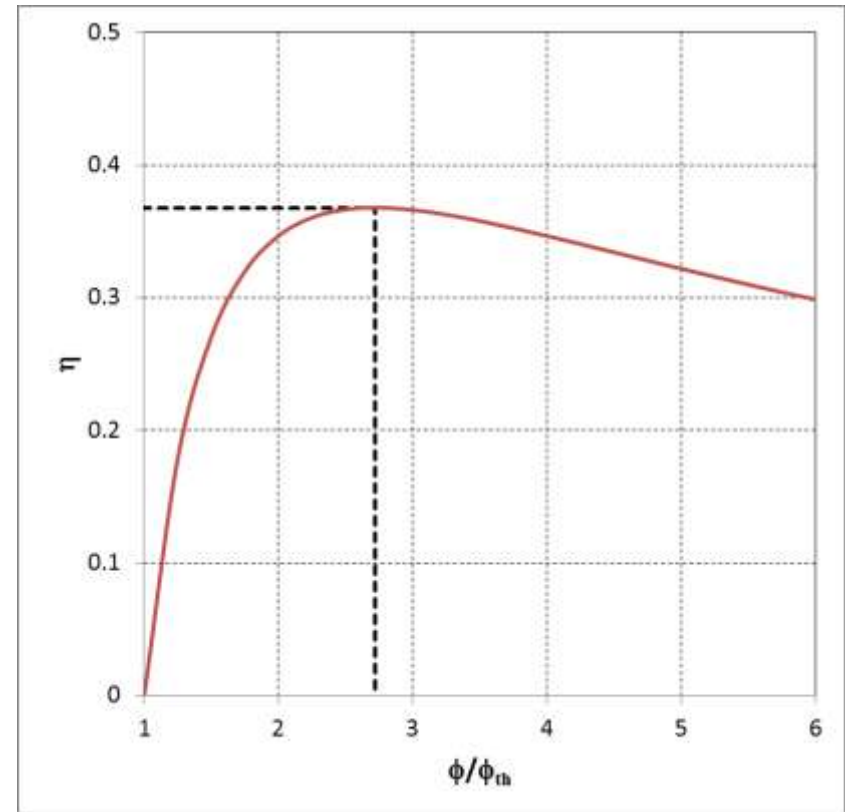
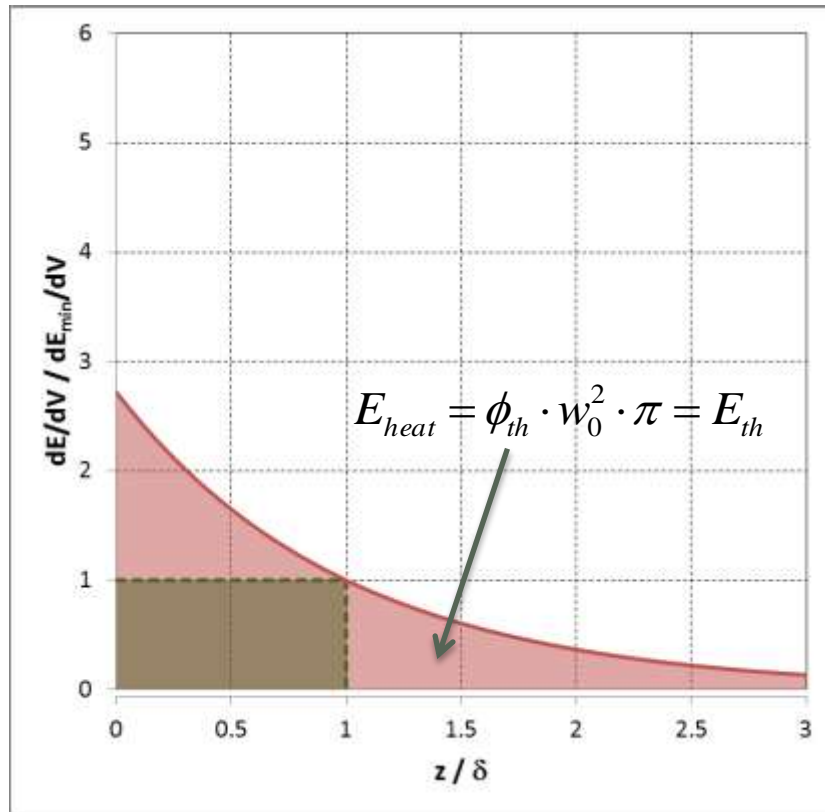
$$z_{abl} = \delta \cdot \ln\left(\frac{\phi}{\phi_{th}}\right)$$

The totally deposited energy corresponds to the red area under the curve, but only the green part is really needed.

The efficiency of the ablation process can be defined by dividing the green by the red area.

$$\eta = \frac{\phi_{th}}{\phi} \cdot \ln\left(\frac{\phi}{\phi_{th}}\right)$$

# Top Hat: Ablation Efficiency

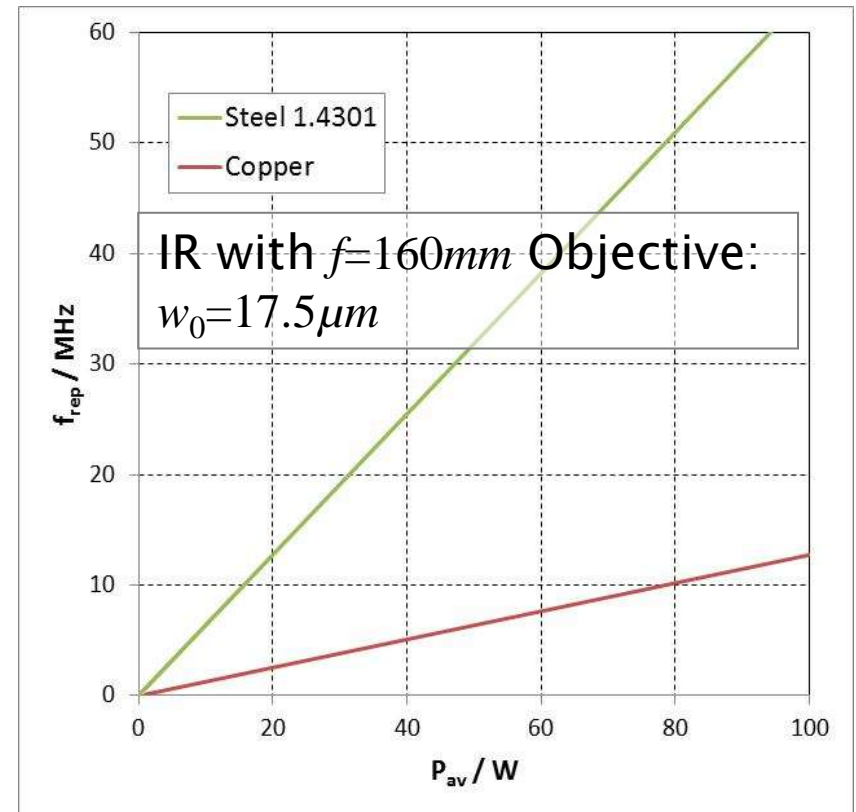
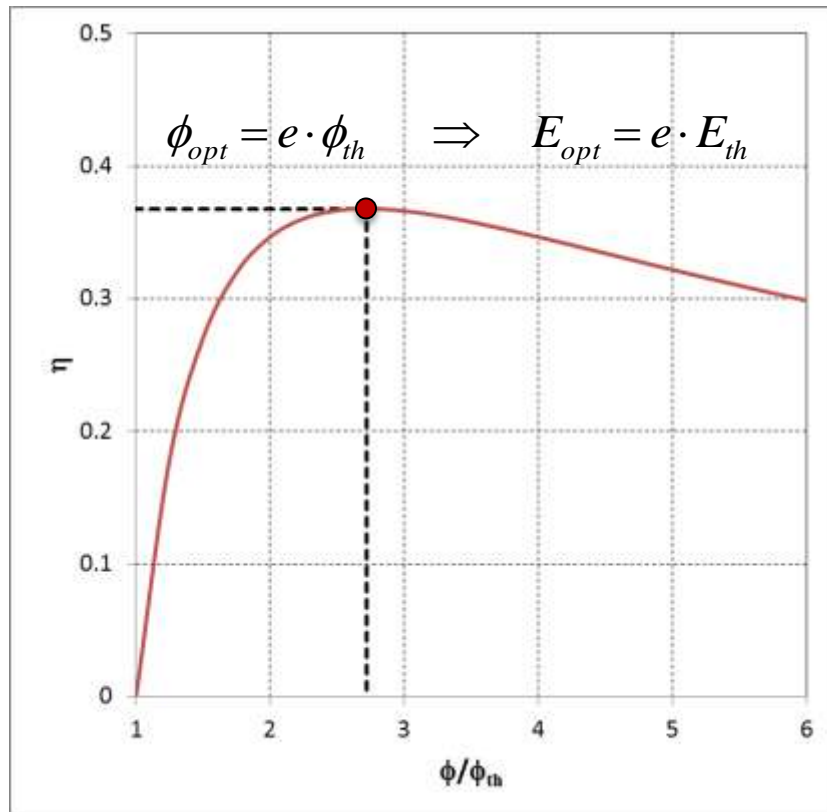


The efficiency  $\eta$  shows a maximum with:  $\eta = 1/e = 36.8\%$  and  $\phi = e \cdot \phi_{th}$

The ablation depth and volume per pulse then read:  $z_{abl} = \delta$

The deposited energy is independent of the pulse energy

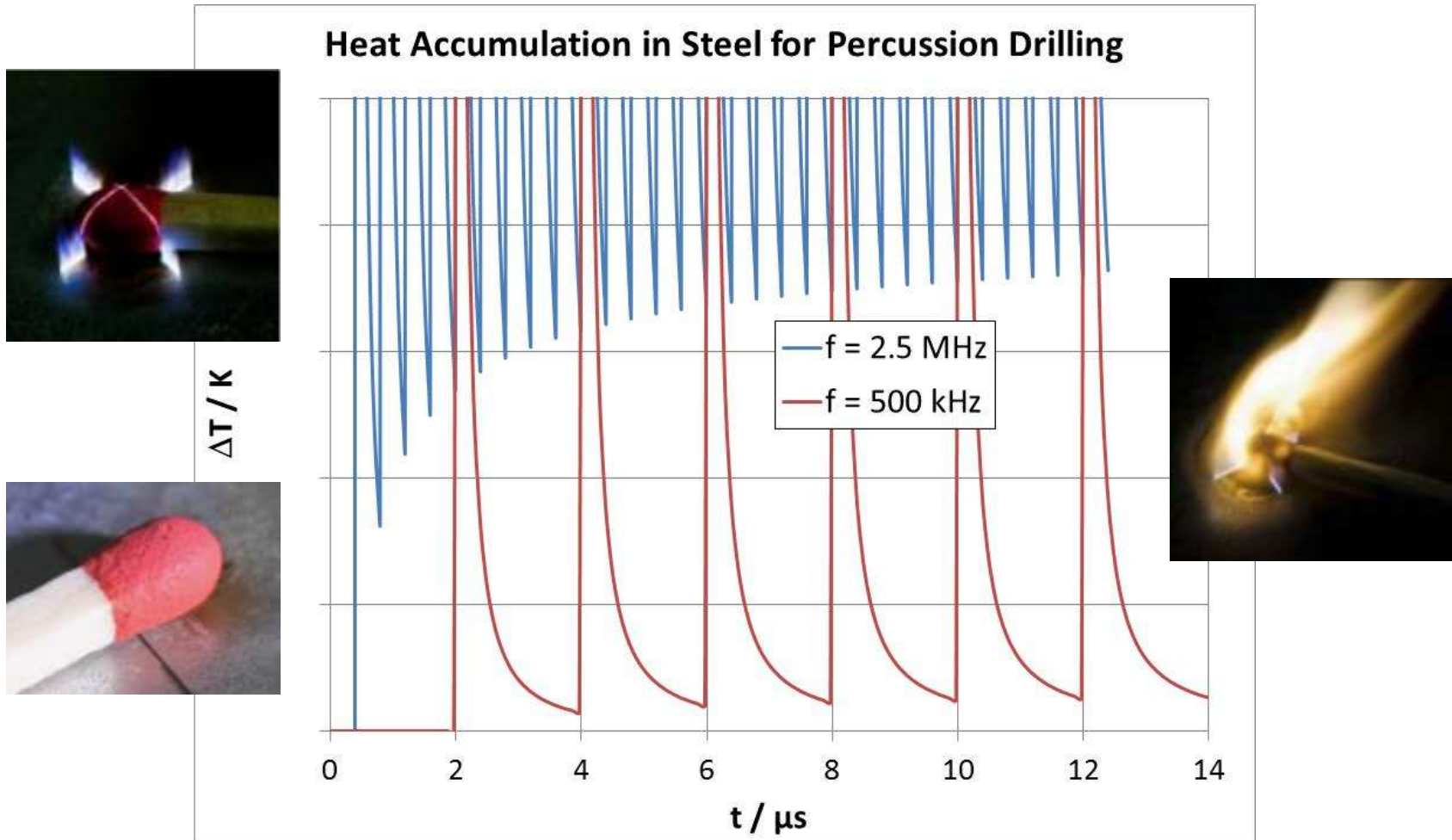
# Top Hat: Optimum Point with Maximum Efficiency



Already at low average powers high repetition rates are demanded to work at the optimum point with maximum efficiency.



# Heat Accumulation versus «Cold Ablation»



For ultra-short pulses “cold” ablation is a question of repetition rate and/or moving speed and not a general property.

# Process – Material - Matrix

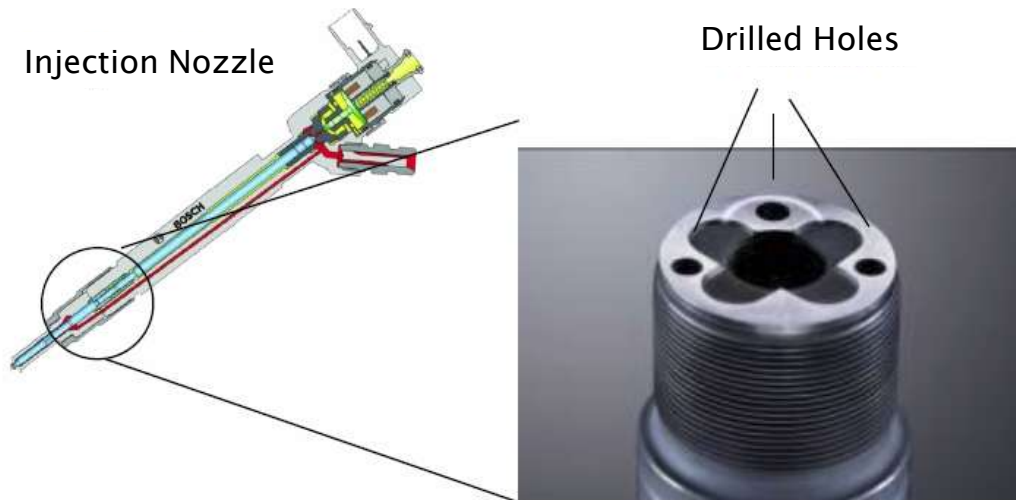
	Metals	Plastics	Glasses & Ceramics	Semiconductors
Master forming				
Shaping				
Separation	Drilling / Marking			
Joining				
Coating				
Material Properties				

Industrialized

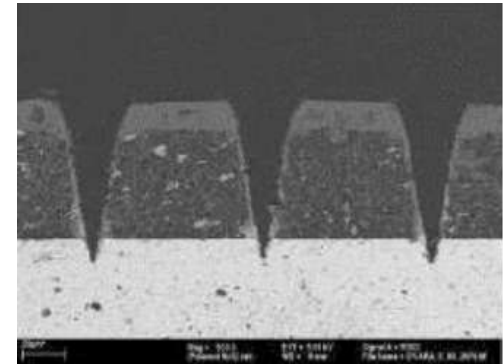
# Industrial Applications

Examples from Bosch:

Drilling of Injection Nozzles:



Marking of defined grooves into a oxygen sensor.



Quellen: Bosch

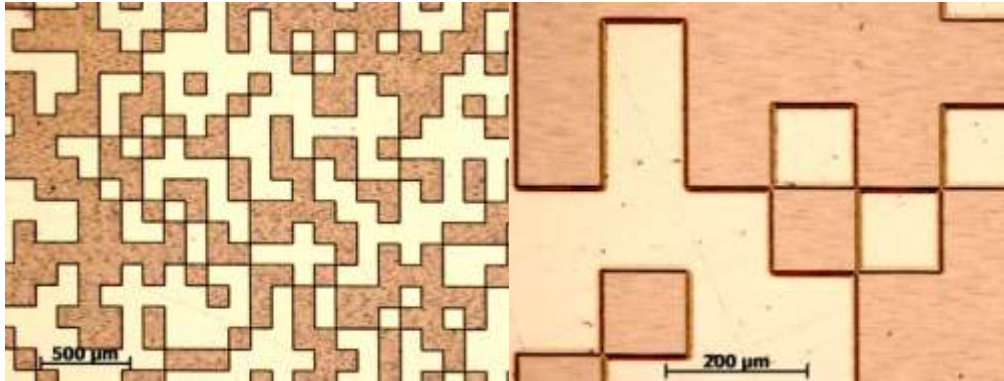
# Process – Material - Matrix

	Metals	Plastics	Glasses & Ceramics	Semiconductors
Master forming				
Shaping				
Separation	Surface - structuring			
Joining				
Coating				
Material Properties				

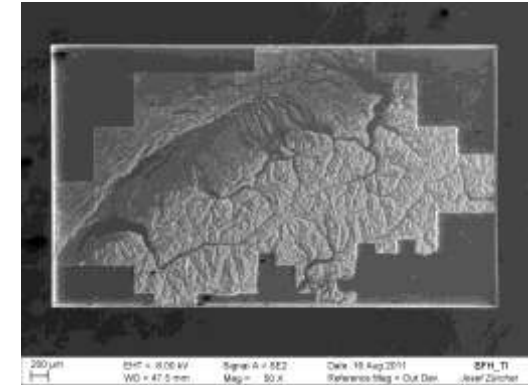
Industrialized & further research

# Surface Structuring

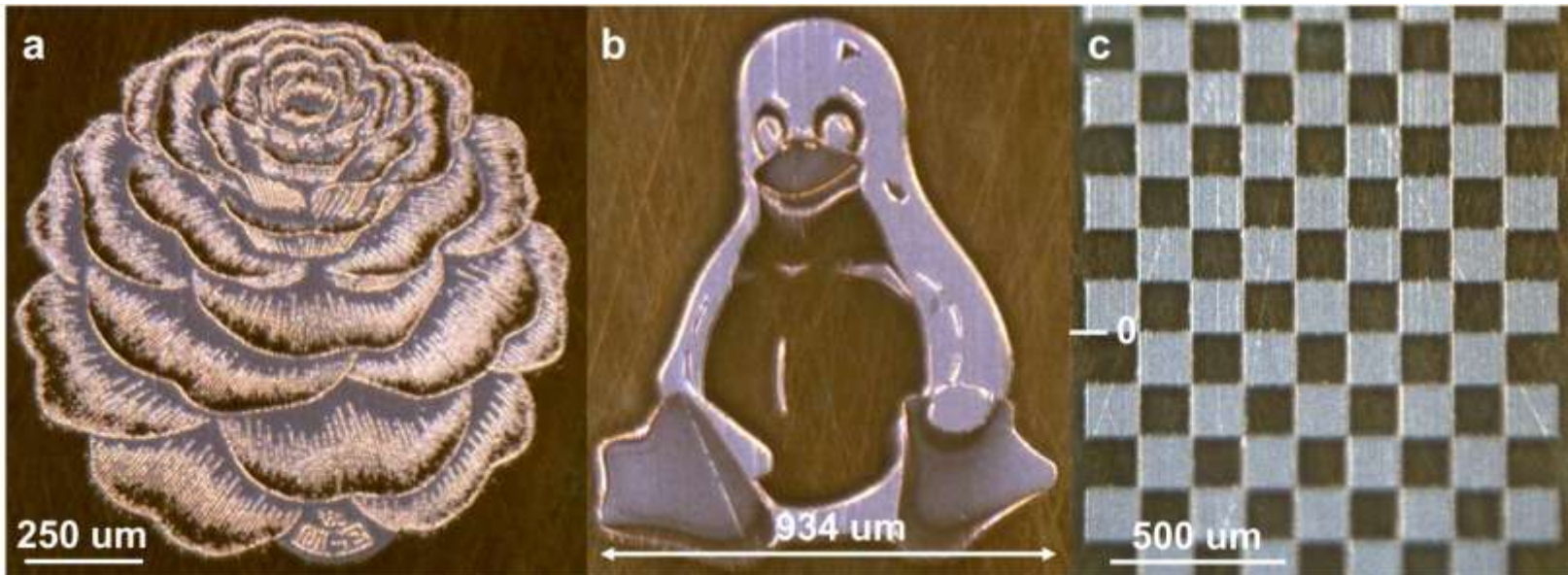
Marking of 2D matrix codes:



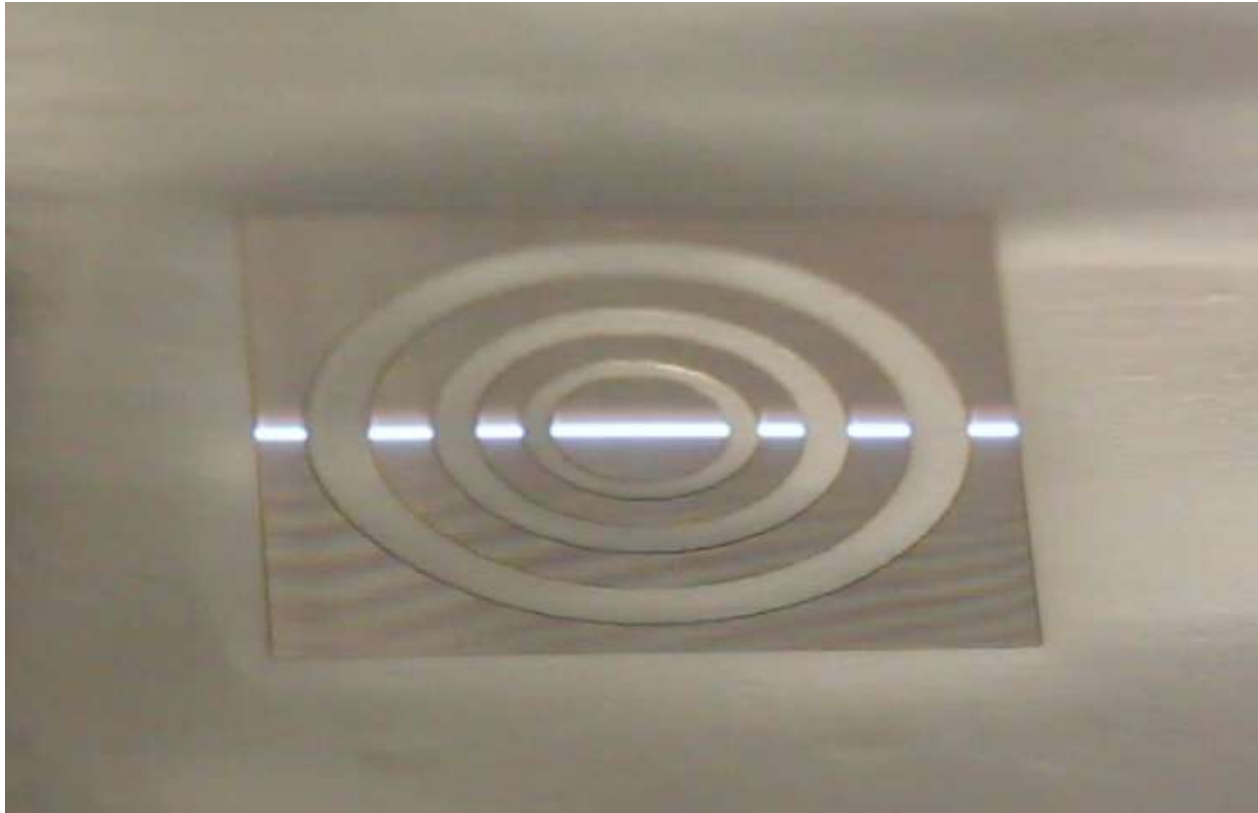
3D Structuring:



Synchronized marking on fast rotating cylinder:

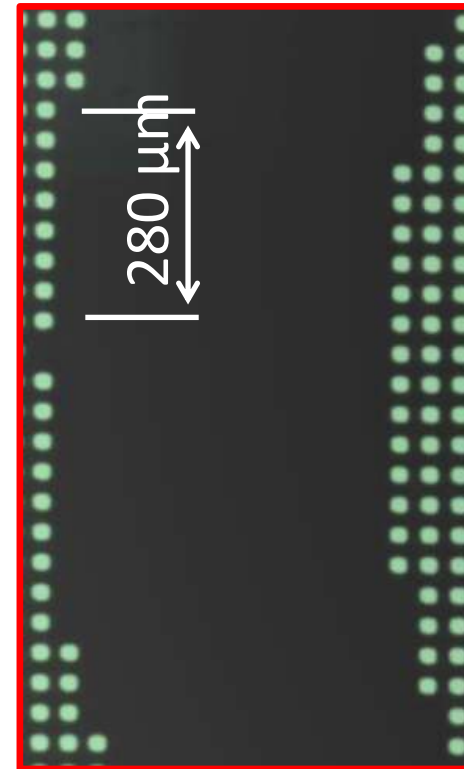
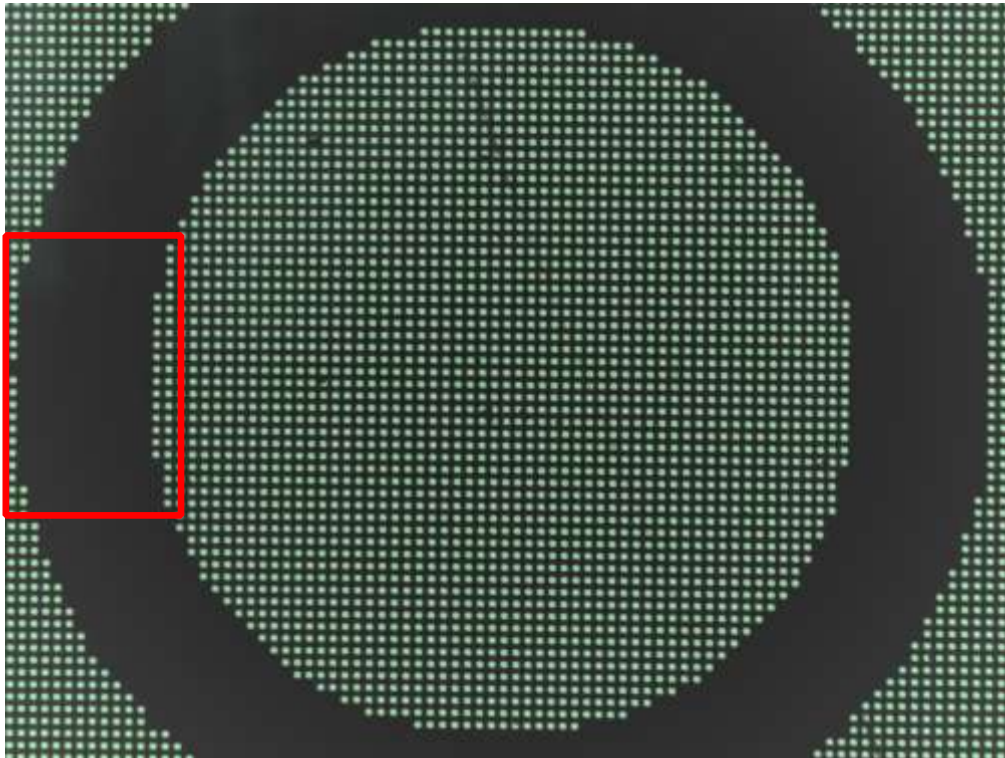


# Multipulse Drilling on the Fly



# Multipulse Drilling on the Fly

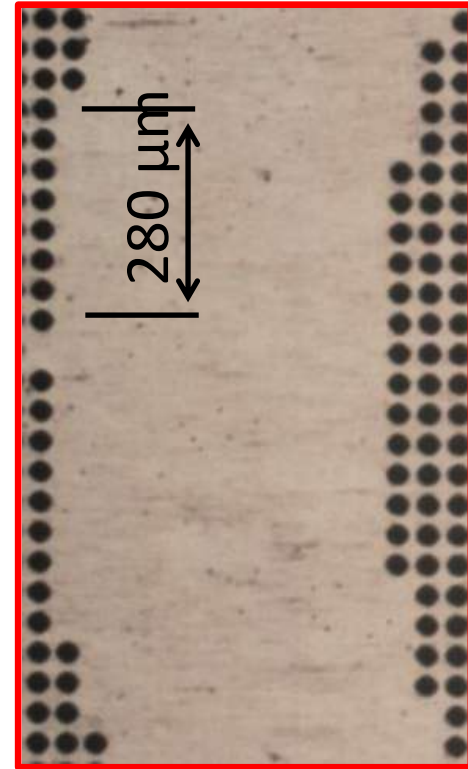
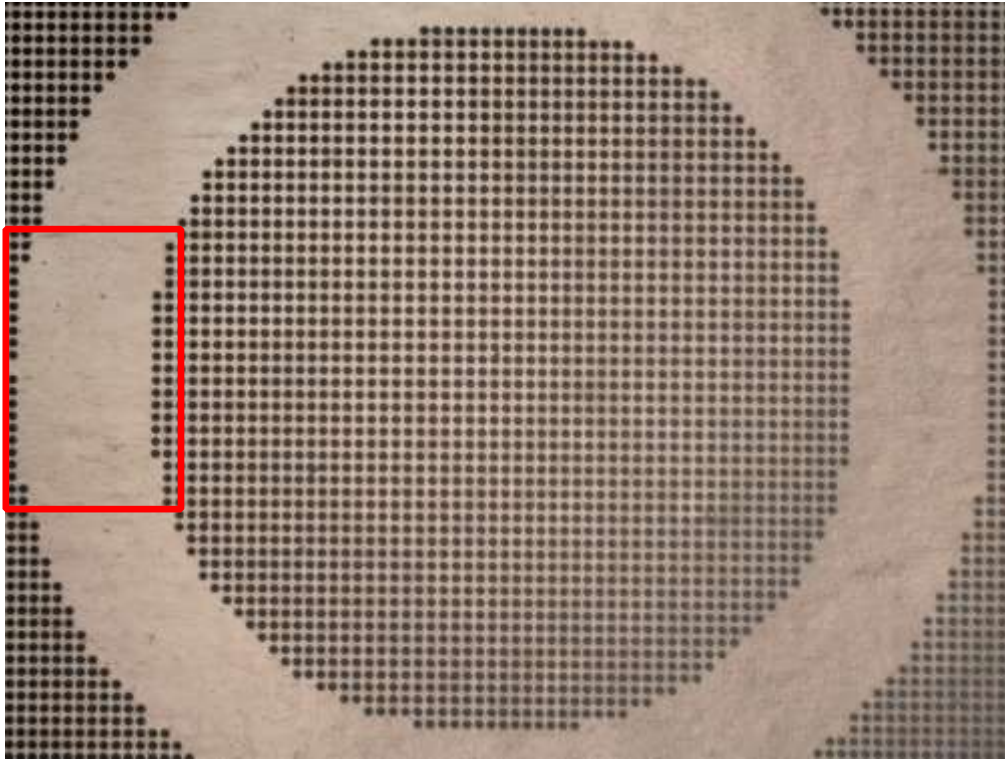
Multi-pulse drilling on the fly, 10  $\mu\text{m}$  steel foil, 1064nm, 900 slices



- ▶ Microscope image of the backside of the sample with green lighted from the frontside
- ▶ Every pixel correspond to one laser shot / drilled hole

# Multipulse Drilling on the Fly

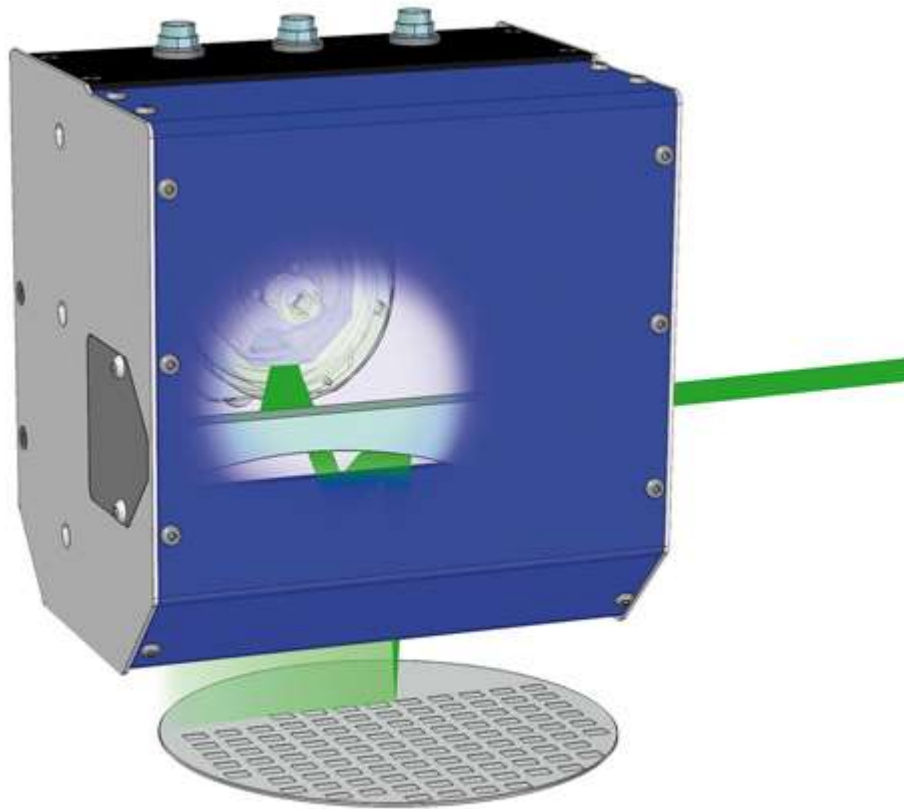
Multi-pulse drilling on the fly, 10  $\mu\text{m}$  steel foil, 1064nm, 900 slices



- ▶ Reflected-light microscope image of the backside
- ▶ No deforming of the thin foil due to heat accumulation



# Fast Synchronized Scanning with Polygon Scanner

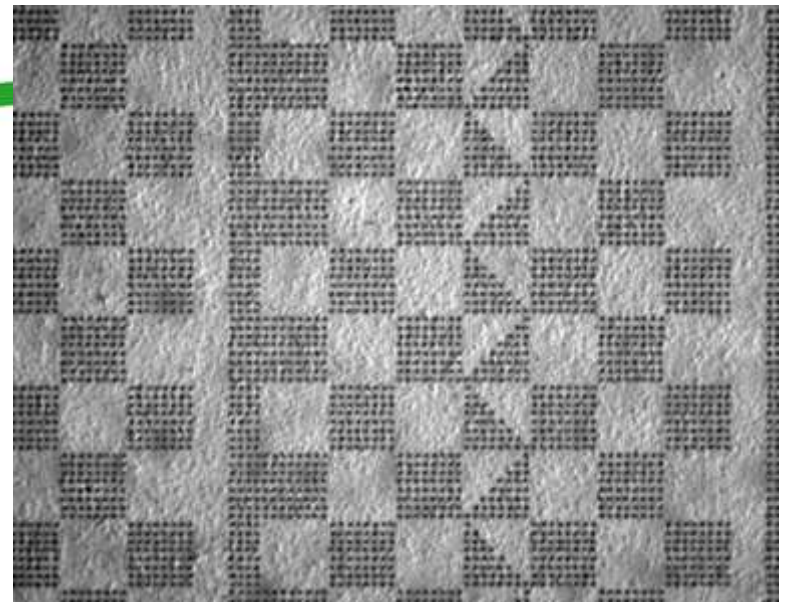


$$w_0 = 11 \mu m \quad @ \quad \lambda = 532 nm$$

$$w_0 = 22 \mu m \quad @ \quad \lambda = 1064 nm$$

$$\ell_{scan} = 170 mm$$

$$v_{max} = 100 m / s$$



Synchronized with FUEGO from  
Time-Bandwidth Products AG

# Fast Synchronized Scanning with Polygon Scanner



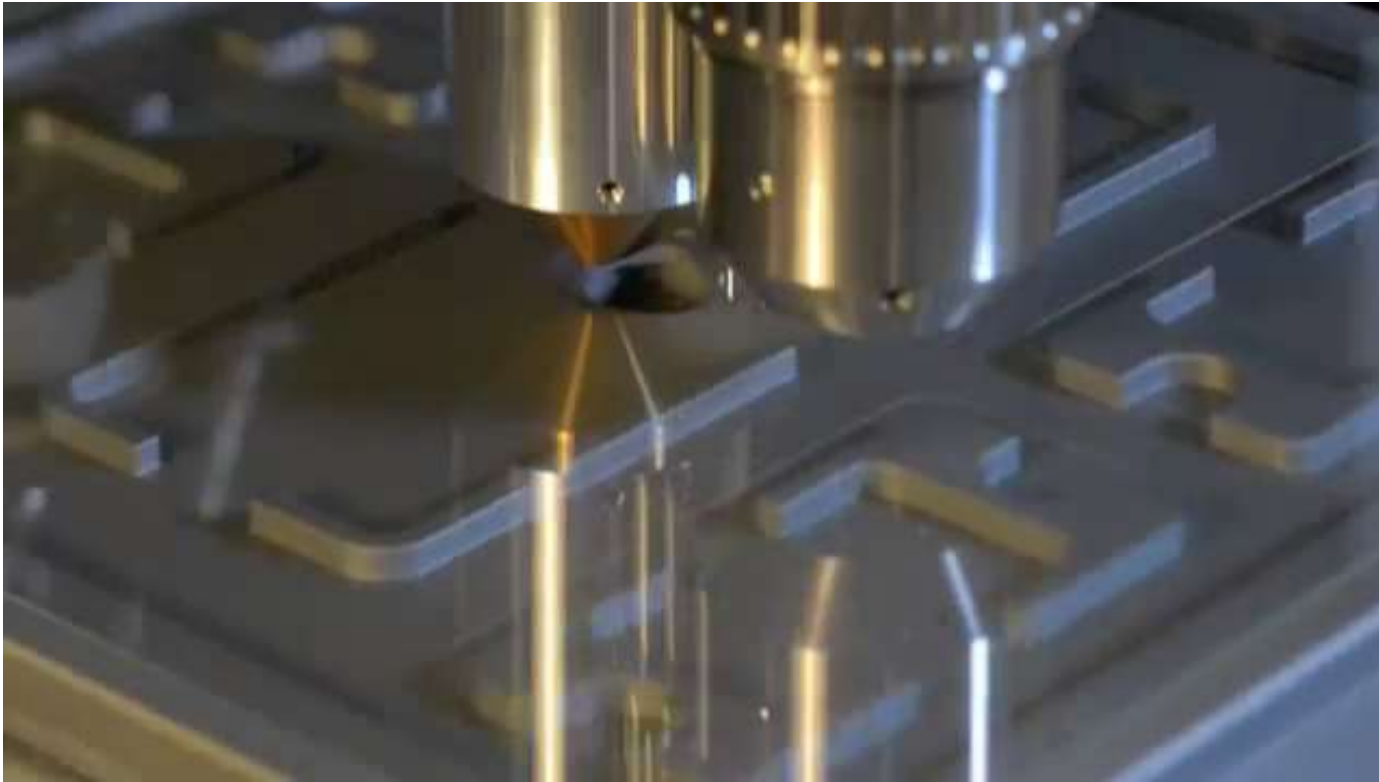
# Process – Material - Matrix

	Metals	Plastics	Glasses & Ceramics	Semiconductors
Master forming				
Shaping				
Separation	Surface - structuring		Glas-Cutting	
Joining				
Coating				
Material Properties				

Industrialized & further research

Applied Research

# Glass and Sapphire Cutting with Bursts



Quelle: Innolas

# Process – Material - Matrix

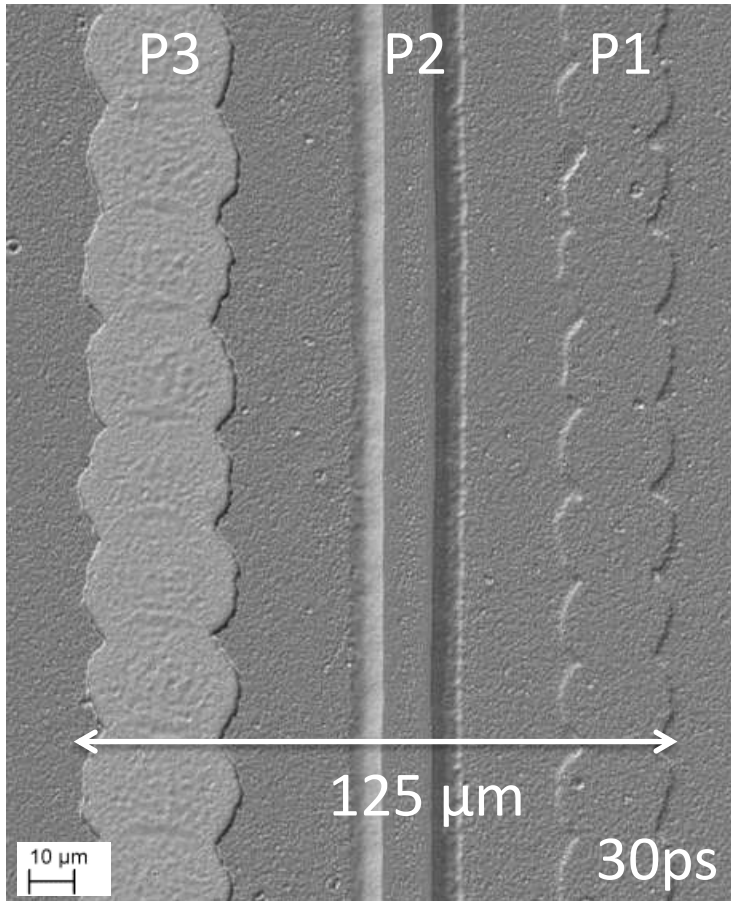
	Metals	Plastics	Glasses & Ceramics	Semiconductors
Master forming				
Shaping				
Separation	Surface - structuring		Glas-Cutting	Laser Scribing of CIGS Solar Cells
Joining				
Coating				
Material Properties				

Industrialized & further research

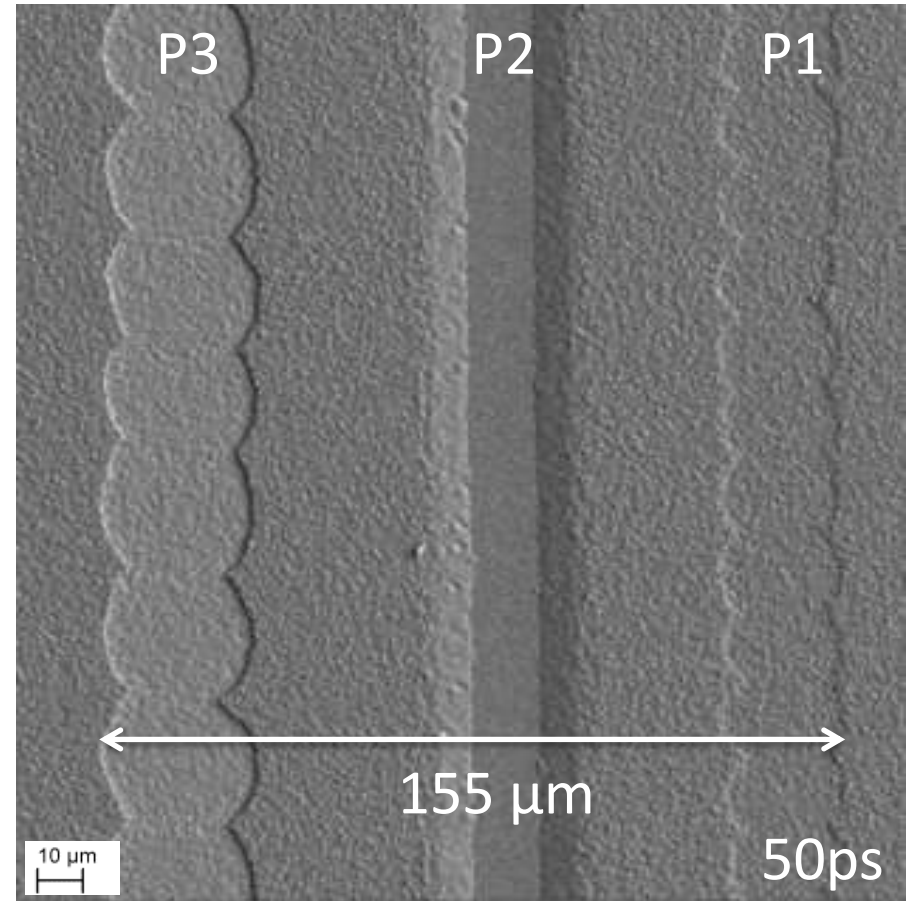
Applied Research

# Scribing of CIGS Solar Cells

fiber laser



SSL



SEM image of complete module interconnect. Similar scribe quality is realized with SSL and fiber laser.

# Process – Material - Matrix

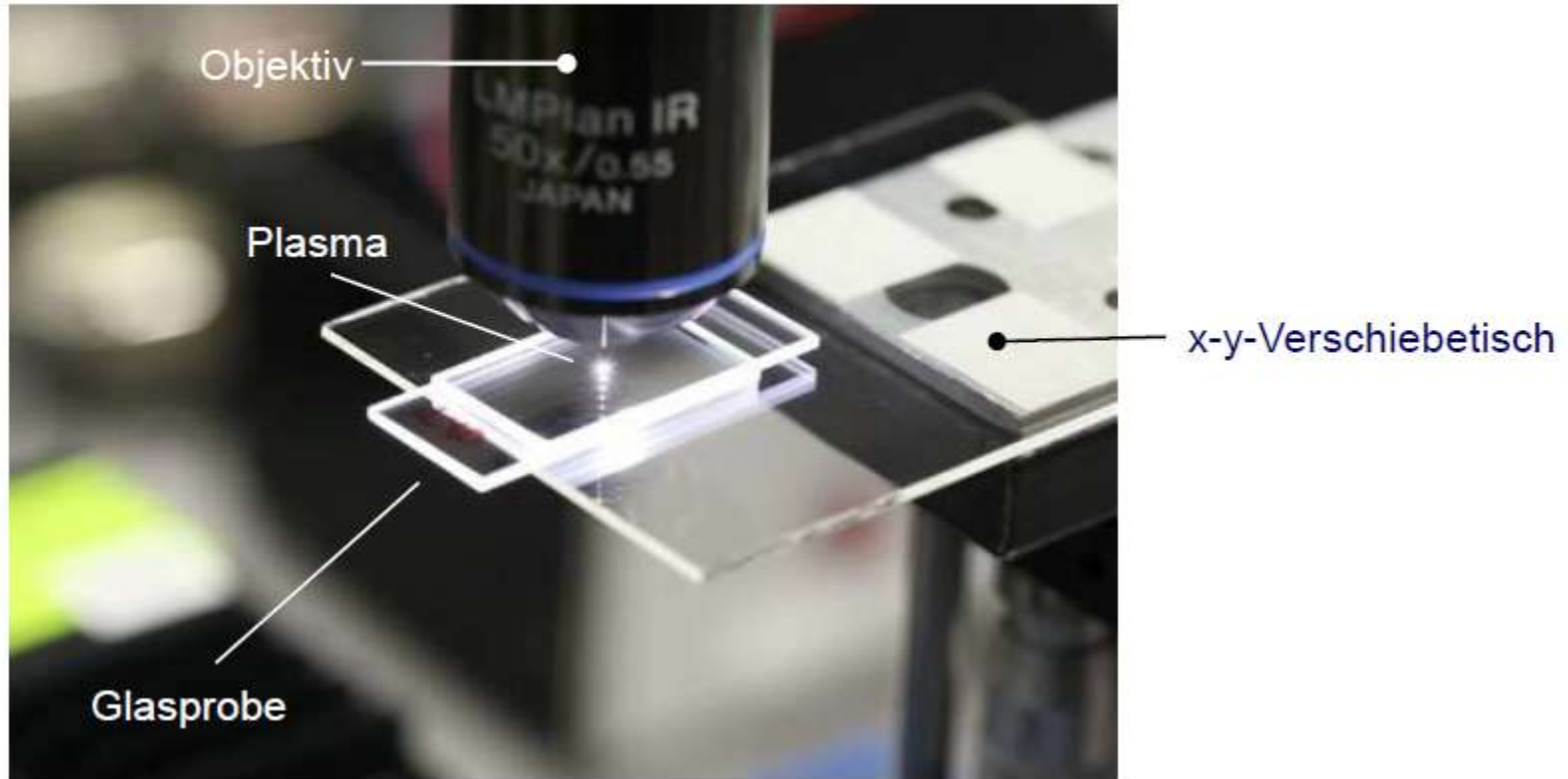
	Metals	Plastics	Glasses & Ceramics	Semiconductors
Master forming				
Shaping				
Separation	Surface - structuring		Glas-Cutting	Laser Scribing of CIGS Solar Cells
Joining			Glass-welding	
Coating				
Material Properties				

Industrialized & further research

Applied Research

# Glass Welding

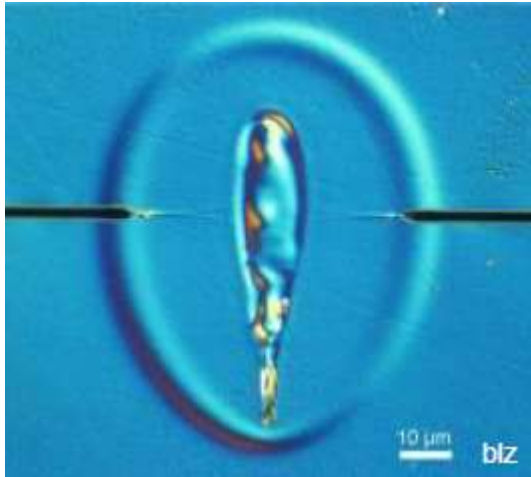
Laser, 10 ps



Quelle: Bayerisches Laserzentrum blz



# Glass Welding



- ▶ Ultra-short pulses produce a plasma in the transparent glass
- ▶ The hot plasma rests within the glass
  - ▶ The plasma heats the environment
  - ▶ A high repetition rate guarantees a hot temperature
- ▶ The melting around the focal point welds the the single glasses

# Process – Material - Matrix

	Metals	Plastics	Glasses & Ceramics	Semiconductors
Master forming				
Shaping	Microshock-wave shaping		Microshock-wave shaping	Microshock-wave shaping
Separation	Ablation / Surface structuring	Surface Structuring	Ablation, Cutting, Surface structuring	Laser Scribing of CIGS Solar Cells, Structuring
Joining	Glass-Metal-Welding		Glass Welding	Glass-Semiconductor Welding
Coating			Coating with LIPPAA Process	
Material Properties			Waveguidescribing Inner Glass Marking	

Industrialized

Applied Research

Future Potential

Ultra-short laser pulses in micro-processing: Myth, a next generation technology or already reality?

It's definitively not a myth

Ultra-short laser pulses in micro-processing: Myth, a next generation technology or already reality?

It's definitively not a myth

Already existing industrialized processes

Ultra-short laser pulses in micro-processing: Myth, a next generation technology or already reality?

It's definitively not a myth

Already existing industrialized processes

Many processes are well on the way to successful industrialization

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Already existing industrialized processes

Many processes are well on the way to successful industrialization

Ultra-short laser pulses are also a promising technology for new applications

Ultra-short laser pulses in micro-processing: Myth, a next generation technology or already reality?

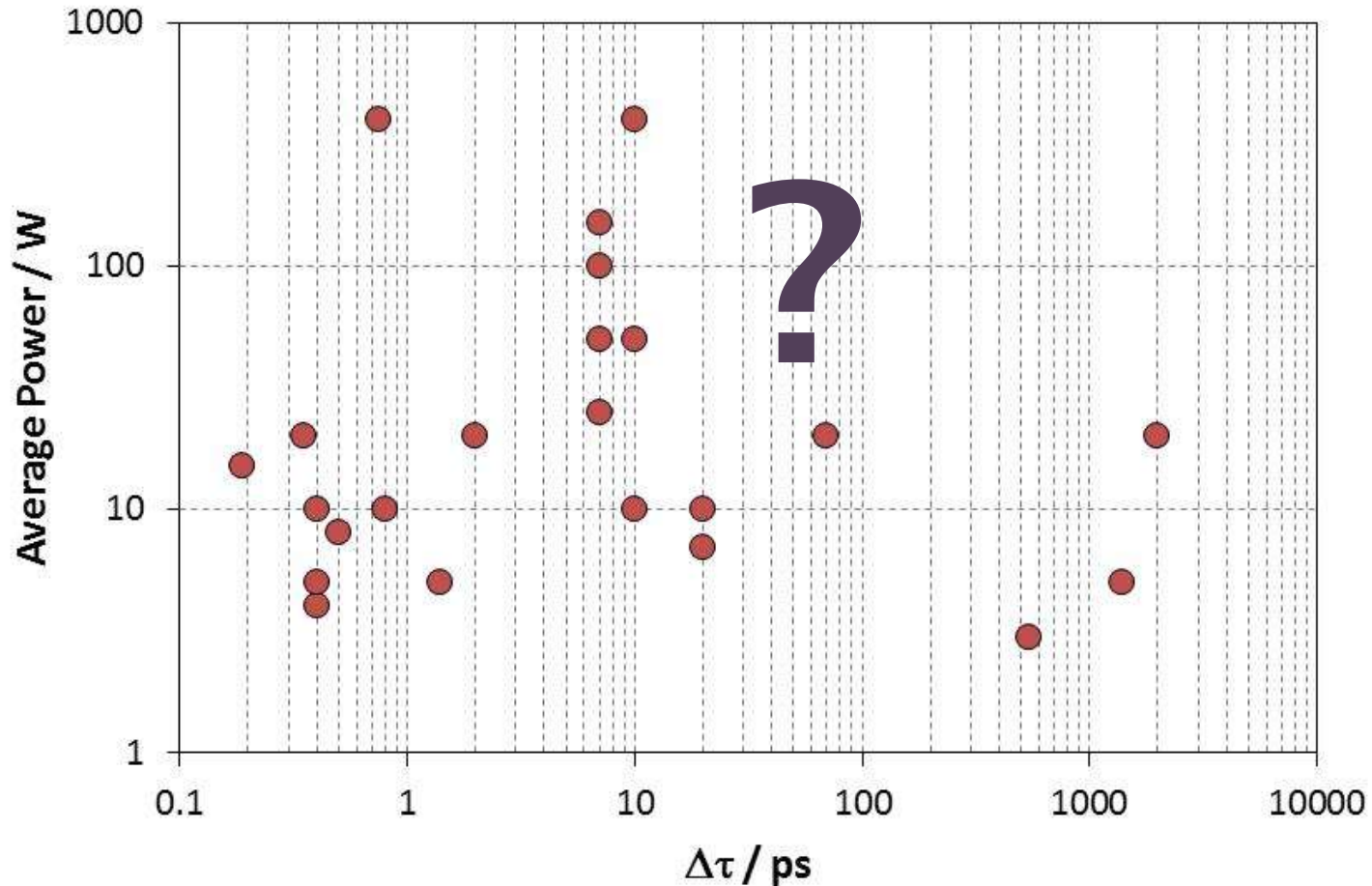
It's definitively not a myth

Already existing industrialized processes

Many processes are well on the way to successful industrialization

Ultra-short laser pulses are also a promising technology for new applications applications

# Ultra-Short Pulsed Systems



A lot of systems with different pulse durations, average powers, wavelengths and pulse energies exist on the market



# SNAPP

Swiss National Application laboratory for Photonic tools and Photonic manufacturing



The main Swiss institutions in laser processing have decided to collaborate to offer the most suitable service to you.

## SNAPP

Swiss National Application laboratory for Photonic tools and Photonic manufacturing

The Swiss material processing industry has expressed interest in a Swiss national application laboratory for photonic tools and photonic manufacturing (SNAPP) for the following reasons

- ▶ near proximity
- ▶ continuity of personnel
- ▶ protection of know how
- ▶ priority of access

The reason for the merger was the pooling of skills and equipment. Each partner has its core competencies. The group can provide extensive consulting and industry work and carry out in joint efforts demanding research projects.

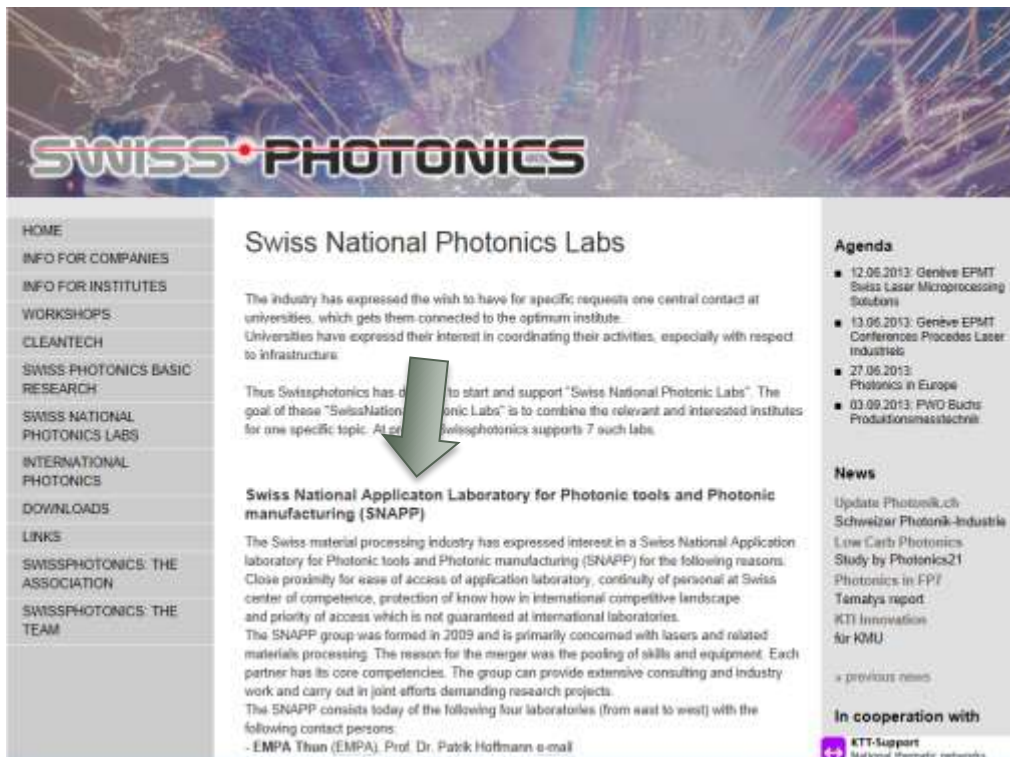
# SNAPP

The SNAPP consists today of the following four laboratories (from east to west) with the following contact persons

- ▶ EMPA Thun and Dübendorf  
Microprocessing with Excimer and ps-Laser  
Prof. Dr. Patrick Hoffmann
- ▶ BFH Burgdorf  
Microprocessing with ultrashort laser pulses, process development and synchronization  
Prof. Dr. Beat Neuenschwander
- ▶ FHNW Windisch  
Microprocessing, 3D engraving, integration  
Beat Lüscher
- ▶ csem Alpnach  
UV-picosecond processing with industrial machine  
Dr. Janko Auerswald
- ▶ inspire ETH Zürich and irpd St. Gallen  
Laser Micro- and Macroprocessing  
Josef Stirnimann

# SNAPP

- ▶ SNAPP has internal meetings in order to be able to provide optimum service to their customers.
- ▶ SNAPP will organize two workshops a year with specific laser processing topics.
- ▶ SNAPP will offer a single entry point for all of your questions.



**Swiss National Photonics Labs**

The industry has expressed the wish to have for specific requests one central contact at universities, which gets them connected to the optimum institute. Universities have expressed their interest in coordinating their activities, especially with respect to infrastructure.

Thus, Swissphotronics has decided to start and support "Swiss National Photonic Labs". The goal of these "Swiss National Photonic Labs" is to combine the relevant and interested institutes for one specific topic. At the moment, Swissphotronics supports 7 such labs.

**Swiss National Applicator Laboratory for Photonic tools and Photonic manufacturing (SNAPP)**

The Swiss material processing industry has expressed interest in a Swiss National Application laboratory for Photonic tools and Photonic manufacturing (SNAPP) for the following reasons: Close proximity for ease of access of application laboratory, continuity of personnel at Swiss center of competence, protection of know how in international competitive landscape and priority of access which is not guaranteed at international laboratories. The SNAPP group was formed in 2009 and is primarily concerned with lasers and related materials processing. The reason for the merger was the pooling of skills and equipment. Each partner has its core competencies. The group can provide extensive consulting and industry work and carry out in joint efforts demanding research projects. The SNAPP consists today of the following four laboratories (from east to west) with the following contact persons:  
- EMPA Thun (EMPA), Prof. Dr. Patrik Hoffmann e-mail

**Agenda**

- 12.06.2012: Genève EPMT Swiss Laser Microprocessing Solutions
- 13.06.2012: Genève EPMT Conferences Procédes Laser Industriels
- 27.06.2012: Photonics in Europe
- 03.09.2012: PWO Buchs Produktionsmesstechnik

**News**

- Update Photonik.ch Schweizer Photonik-Industrie
- Low Carb Photonics Study by Photonics21
- Photonics in FPF
- Tamalya report: KIT Innovation für KMU

◀ previous news

**In cooperation with**

KIT-Support National thematic networks

- ▶ Go to: [www.swissphotonics.net](http://www.swissphotonics.net)
- ▶ Select SWISS NATIONAL PHOTONCS LABS
- ▶ Find SNAPP information and contacts